

Amendments to the claims:

The listing of claims set forth below replace all prior versions in the listings of claims in the subject application:

In the Claims:

Claim 1 (Previously Amended) An abrasive composition for polishing substrates comprising:

a plurality of colloidal silica abrasive particles comprising a polydisperse particle size distribution with a median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles, and wherein the span value is measured by subtracting the d_{10} particle size of the colloidal silica particles from the d_{10} particle size of the colloidal silica particles.

Claim 2 (Previously Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 15% by volume of the abrasive particles.

Claim 3 (Previously Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 10% by volume of the abrasive particles.

Claim 4 (Previously Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles.

Claim 5 (Previously Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 18 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles.

Claim 6 (Previously Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 20 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles.

Claim 7 (Previously Amended) An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 22 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles.

Claim 8 (Canceled).

Claim 9 (Canceled).

Claim 10 (Canceled).

Claim 11 (Previously Amended) An abrasive slurry composition for polishing substrates comprising:

a plurality of colloidal silica abrasive particles comprising a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, and a span value, by volume, being greater than or equal to 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles, and wherein the span value is measured by subtracting the d_{10} particle size of the colloidal silica particles from the d_{10} particle size of the colloidal silica particles; and

a solution having one or more chemical reactants.

Claim 12 (Previously Amended) An abrasive slurry according to claim 11, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 10% by volume of the abrasive particles.

Claim 13 (Previously Amended) An abrasive slurry according to claim 11, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 18 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles.

Claim 14 (Previously Amended) An abrasive slurry according to claim 11, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume,

being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 20 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles.

Claim 15 (Canceled).

Claim 16 (Canceled).

Claim 17 (Previously Amended) A method for polishing substrates with an abrasive composition comprising:

providing a substrate to be polished;
and polishing the substrate using a plurality of colloidal silica abrasive particles comprising, a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles, and wherein the span value is measured by subtracting the d_{10} particle size of the colloidal silica particles from the d_{90} particle size of the colloidal silica particles.

Claim 18 (Previously Amended) A method according to claim 17, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 10% by volume of the abrasive particles.

Claim 19 (Previously Amended) A method according to claim 17, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or

equal to about 18 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles.

Claim 20 (Previously Amended) A method according to claim 17, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 20 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles.

Claim 21 (Canceled).

Claim 22 (Canceled).

Claim 23 (Previously Presented) An abrasive composition according to Claim 1, wherein the span value, by volume, is at least 25 nanometers.

Claim 24 (Previously Presented) An abrasive composition according to Claim, wherein the span value, by volume, is at least 30 nanometers.

Claim 25 (New) An abrasive composition for polishing substrates comprising:

a plurality of abrasive particles consisting essentially of colloidal silica particles comprising a polydisperse particle size distribution with a median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles, and wherein the span value is measured by subtracting the d_{10} particle size of the colloidal silica particles from the d_{10} particle size of the colloidal silica particles.

Claim 26 (New) An abrasive slurry composition for polishing substrates comprising:

a plurality of silica abrasive particles consisting essentially of colloidal silica particles comprising a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, and a span value, by volume, being greater than or equal to 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is from greater than about 0% to less than or equal to about 20% by volume of the abrasive particles, and wherein the span value is measured by subtracting the d_{10} particle size of the colloidal silica particles from the d_{10} particle size of the colloidal silica particles; and

a solution having one or more chemical reactants.